

ABSTRACT OF THE DISCLOSURE

To provide a cleaning processing method and a cleaning processing apparatus which can improve cleaning efficiency.

- 5       The apparatus is structured to install processing units 11a - 11d which provide more than one kind of chemical liquids out of a plurality of chemical liquids A - C for processing wafers W, and to enable the same kind of a processing liquid to be provided for at least two processing
- 10       units, and, upon successively processing objects-to-be-processed which require their own processing sequences, to consecutively load each object-to-be-processed W to a processing unit which stores designated chemical liquid for a processing sequence of the object-to-be-processed.